THE CHINESE UNIVERSITY OF HONG KONG
DEPARTMENT OF ELECTRONIC ENGG
Microfabrication Laboratory
TEL: (852) 3163 4307 FAX: (852) 2603 5558

LIST OF CHARGES – Feb, 2009

Charges for Using Equipment/Instruments in Microfabrication Lab

Equipment/ Instrument	Industry or Government Rate		Institutions (HK$ / Hourly Rate)	
	Equipment Charge (HK$/Hourly Rate)	Operator Charge (HK$/Hourly Rate)	Equipment Charge (HK$/Hourly Rate)	Operator Charge (HK$/Hourly Rate)
ICP Silicon dry etcher	650	350	350	350
Photolithographic	300+ 100/4hours N2	350	200+ 100/4hours N2	350
Plasma Etching	300	350	150	350
Thin Film Deposition -sputtering	200	250	100	250
Thin Film Deposition –e-beam	200	250	100	250
High Temperature furnace	200	250	100	250
Rapid temperature annealing	200	250	100	250
Vacuum Annealing	200	250	100	250
CleanRoom usage (etching, thickness measurement….)	350/4hours	/	150/4hours	/

CU user will be discount to 50% of institutions price